

Tuning MoCl_5 Self-Etching Effect for Deposition of 2D MoS_2 on 300mm Wafer by Thermal ALD

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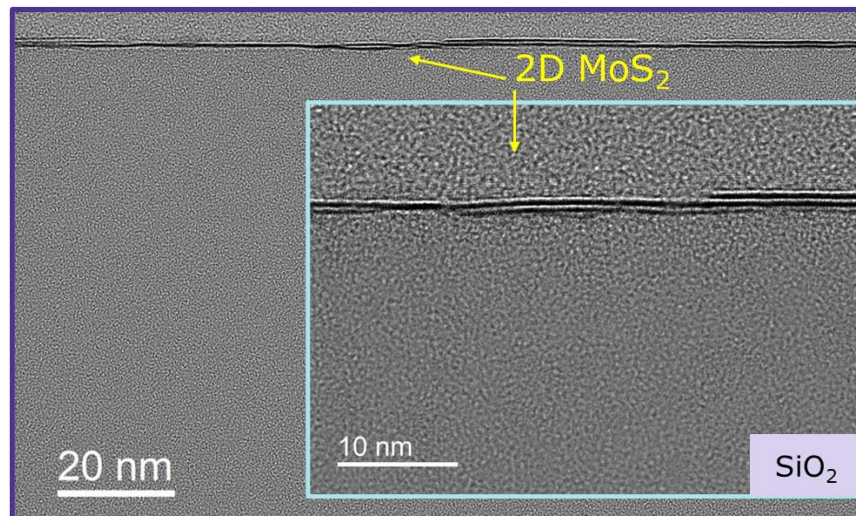


Fig. 1. Cross-section TEM image of 2D MoS_2 deposited on $3\text{k}\text{\AA}$ SiO_2/Si substrate by MoCl_5 -based thermal ALD.